

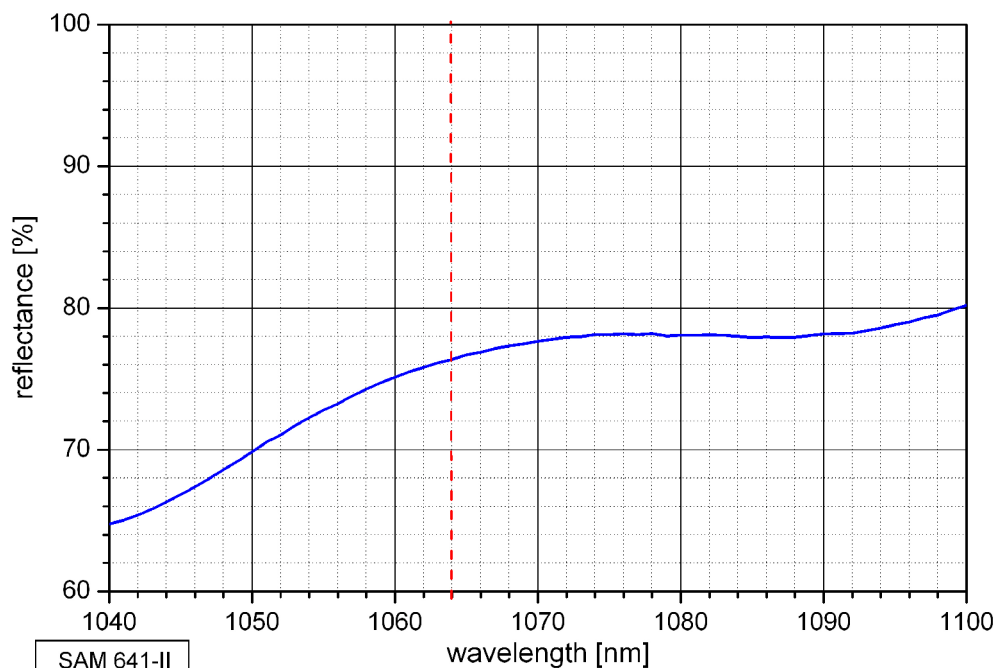
SAM™ Data Sheet SAM-1064-23-124ps-x, $\lambda = 1064$ nm for microchip laser Q-switching

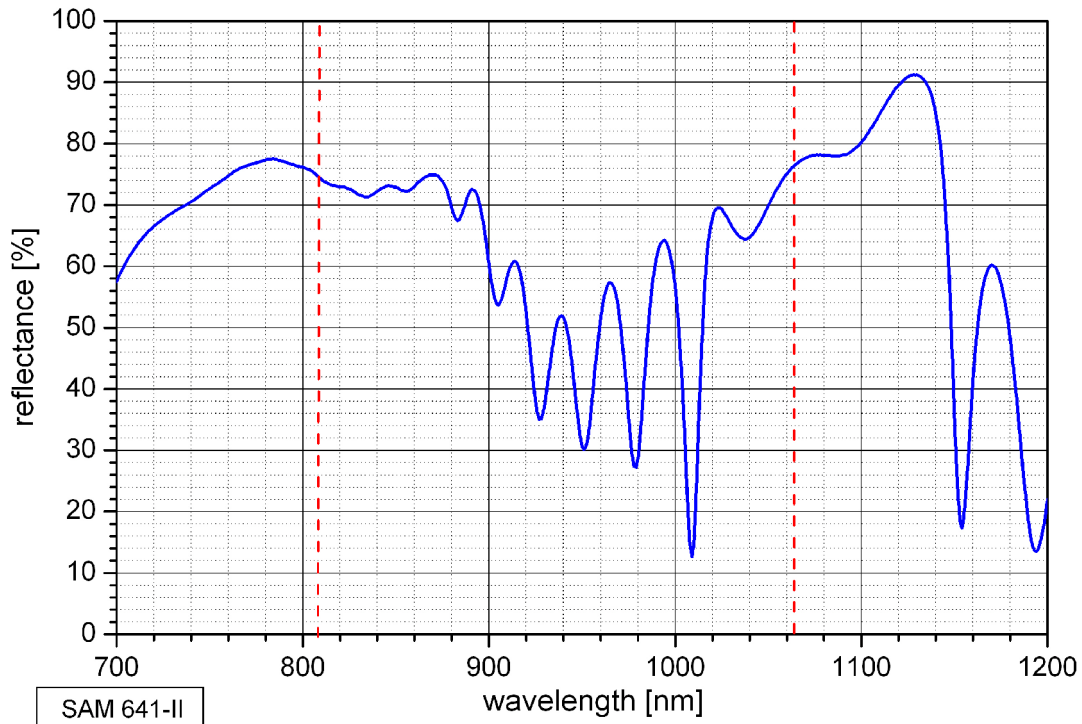
Laser wavelength	$\lambda = 1064$ nm
High reflection band (R > 70%)	$\lambda = 1050 \dots 1100$ nm
Reflectance at 808 nm	$R_{808} = 75$ %
Absorbance	$A_0 = 23$ %
Modulation depth	$\Delta R = 12$ %
Non-saturable loss	$A_{ns} = 11$ %
Saturation fluence	$\Phi_{sat} = 70$ $\mu\text{J}/\text{cm}^2$
Relaxation time constant	$\tau \sim 124$ ps
Damage threshold	500 MW/cm ²
Chip area	4mm x 4mm; other dimensions on request
Chip thickness	450 μm
Dielectric coating	HR @ 808 nm

Mounting option **x** denotes the type of mounting as follows:

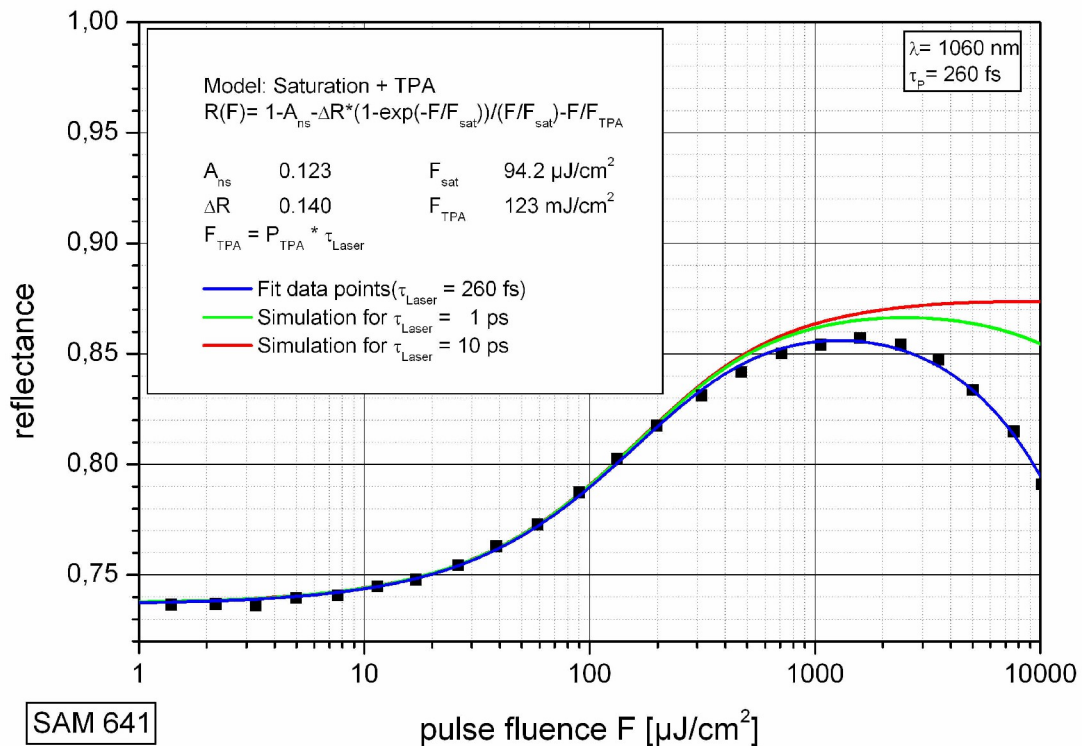
x = 0	unmounted
x = 12.7 g	glued on a copper heat sink with 12.7 mm \varnothing
x = 25.4 g	glued on a copper heat sink with 25.4 mm \varnothing
x = 12.7 s	soldered on a copper heat sink with 12.7 mm \varnothing
x = 25.4 s	soldered on a copper heat sink with 25.4 mm \varnothing
x = 25.4 w	soldered on a water cooled copper heat sink with 25.4 mm \varnothing
x = FC	mounted on a 1 m single mode fiber cable with FC connector

Low intensity spectral reflectance





Saturation measurement without dielectric coating



The saturation measurement has been done using a pulsed laser source with 260 fs pulse duration on a piece from the same wafer # 641, but other dielectric coating with lower absorption and higher saturation fluence. Due to the high peak power density the two photon absorption (TPA) is significant in

this case. The green and red curves are simulated for the same pulse fluences, but longer pulse durations of 1 ps and 10 ps respectively..

Pump-probe measurement

